

Title (en)

METHOD AND APPARATUS FOR METAL OXIDE CHEMICAL VAPOR DEPOSITION ON A SUBSTRATE SURFACE

Title (de)

VERFAHREN UND GERÄT ZUR CHEMISCHEN ABSCHIEDUNG VON METALLOXIDEN AUS DER GASPHASE ALS SCHICHT AUF EINE SUBSTRATOBERFLÄCHE

Title (fr)

PROCEDE ET APPAREIL DE DEPOT CHIMIQUE EN PHASE VAPEUR D'OXYDE METALLIQUE SUR UNE SURFACE DE SUBSTRAT

Publication

**EP 1189706 A1 20020327 (EN)**

Application

**EP 00915975 A 20000228**

Priority

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- US 27203699 A 19990318

Abstract (en)

[origin: WO0054893A1] A method and apparatus for improved metal oxide chemical vapor deposition on a substrate surface where the application boundary layer is reduced and where the uniformity of the application boundary layer is greatly enhanced in a reactor (14). Primary and secondary sonic or other disturbance sources (32, 34) are introduced to the interior chamber or an oscillating chuck (22) is incorporated to influence the boundary layer thickness and uniformity.

IPC 1-7

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IPC 8 full level

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CPC (source: EP US)

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